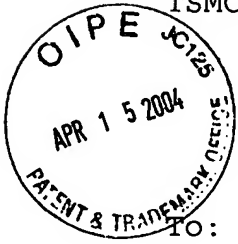


TSMC-01-039C



April 5, 2004

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject:

Serial No. 10/798,992 03/12/04

Shu-Ying Cho et al.

THE ANTI-TYPE DOSAGE AS LDD IMPLANT

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on April 12, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 4/12/04

TSMC-01-039C

U.S. Patent 5,538,914 to Chiu et al., "LDD Method of Coding Mask ROM Device and LDD Coded Mask ROM Device Produced Thereby," discloses a method of programming or coding a mask-ROM.

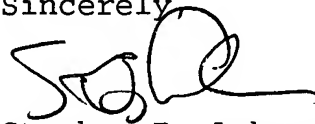
U.S. Patent 6,133,101 to Wu, "Low Mask Count Process to Fabricate Mask Read Only Memory Devices," discloses a method of forming a mask ROM.

U.S. Patent 6,087,699 to Wann et al., "Laminated Gate Mask ROM Device," discloses a laminated gate mask ROM.

U.S. Patent 5,940,710 to Chung et al., "Method for Fabricating Metal Oxide Semiconductor Field Effect Transistor," teaches a method for fabricating a metal oxide semiconductor field effect transistor (MOSFET).

U.S. Patent 5,480,822 to Hsue et al., "Method of Manufacture of Semiconductor Memory Device with Multiple, Orthogonally Disposed Conductors," discloses a memory device with multiple and orthogonally disposed conductors.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', is written over the typed name.

Stephen B. Ackerman,
Reg. No. 37761

Group 1st Unit

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered; Forbids entry of this form with next communication to the applicant.